WEST Search History

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DATE: Tuesday, March 13, 2007

DB=USPT; PLUR=YES; OP=ADJ L13 L12 and 19 L12 (apparatus or tank) same overflow\$3 same ((suply\$3 or inlet or feed\$3) with (bottom or lower)) same (control or valve) DB=PGPB, USPT; PLUR=YES; OP=ADJ L11 L9 and 17 DB=USPT; PLUR=YES; OP=ADJ L10 L9 and 17 L9 134/56R,94.1,186,902,18.ccls. DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ (apparatus or tank) same overflow\$3 same ((suply\$3 or inlet or feed\$3) with (bottom or lower)) same (control or valve) same (semiconductor or substrate or article or wafer) DB=PGPB, USPT, USOC, EPAB,JPAB, DWPI, PLUR=YES; OP=ADJ (apparatus or tank) same overflow\$3 same ((suply\$3 or inlet or feed\$3) with (bottom or lower)) same (control or valve) same (semiconductor or substrate or article or wafer) L6 (bottom or lower)) same (control or valve) same (semiconductor or substrate or article or wafer) L6 L5 and ((apparatus or tank) same overflow\$3 same ((suply\$3 or inlet or feed\$3) with (bottom or lower)) same (control or valve)) L5 l4 or l3 or l2 or l1 L4 (dainippon screen mfg).as. L5 nagami-shuzo\$.in. L1 araki-hiroyuki\$.in. 267	Hide?	<u>Set</u> Name	Query	<u>Hit</u> <u>Count</u>
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□ L11 L9 and 17 1 DB=USPT; PLUR=YES; OP=ADJ 1 □ L10 L9 and 17 1 □ L9 134/56R,94.1,186,902,18.ccls. 3245 DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ (apparatus or tank) same overflow\$3 same ((suply\$3 or inlet or feed\$3) with □ L8 (bottom or lower)) same (control or valve) same (semiconductor or substrate or article or wafer) 6 DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ (apparatus or tank) same overflow\$3 same ((suply\$3 or inlet or feed\$3) with □ L7 (bottom or lower)) same (control or valve) same (semiconductor or substrate or article or wafer) 171 □ L5 and ((apparatus or tank) same overflow\$3 same ((suply\$3 or inlet or feed\$3) with (bottom or lower)) same (control or valve)) 2 □ L5 I4 or I3 or I2 or I1 11780 □ L4 (dainippon screen mfg).as. 11600 □ L3 nagami-shuzo\$.in. 12 □ L2 ogushi-ryotaro\$.in. 1		L12		503
DB=USPT; PLUR=YES; OP=ADJ □ L10 L9 and 17		DB=B	PGPB, USPT; PLUR=YES; OP=ADJ	
□ L10 L9 and 17 1 □ L9 134/56R,94.1,186,902,18.ccls. 3245 DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ (apparatus or tank) same overflow\$3 same ((suply\$3 or inlet or feed\$3) with 6 □ L8 (bottom or lower)) same (control or valve) same (semiconductor or substrate or article or wafer) 6 DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ (apparatus or tank) same overflow\$3 same ((suply\$3 or inlet or feed\$3) with 171 □ L7 (bottom or lower)) same (control or valve) same (semiconductor or substrate or article or wafer) 171 □ L5 and ((apparatus or tank) same overflow\$3 same ((suply\$3 or inlet or feed\$3) with (bottom or lower)) same (control or valve)) 2 □ L5 l4 or l3 or l2 or l1 11780 □ L4 (dainippon screen mfg).as. 11600 □ L3 nagami-shuzo\$.in. 12 □ L2 ogushi-ryotaro\$.in. 1		L11	L9 and 17	, 1
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 □ L7 (bottom or lower)) same (control or valve) same (semiconductor or substrate or article or wafer) □ L6 L5 and ((apparatus or tank) same overflow\$3 same ((suply\$3 or inlet or feed\$3) with (bottom or lower)) same (control or valve)) □ L5 l4 or l3 or l2 or l1 l1780 □ L4 (dainippon screen mfg).as. l1600 □ L3 nagami-shuzo\$.in. l2 □ L2 ogushi-ryotaro\$.in. l1 		DB=I	PGPB, USPT, USOC, EPAB, JPAB, DWPI; PLUR=YES; OP=ADJ	
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 □ L4 (dainippon screen mfg).as. □ L3 nagami-shuzo\$.in. □ L2 ogushi-ryotaro\$.in. 1 		L6		2
□ L3 nagami-shuzo\$.in. 12 □ L2 ogushi-ryotaro\$.in. 1		L5	14 or 13 or 12 or 11	11780
L2 ogushi-ryotaro\$.in.		L4	(dainippon screen mfg).as.	11600
		L3	nagami-shuzo\$.in.	12
☐ L1 araki-hiroyuki\$.in. 267		L2	ogushi-ryotaro\$.in.	1
		L1	araki-hiroyuki\$.in.	267

END OF SEARCH HISTORY